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纳米SiO₂的制备及性能研究

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Synthesis and characterization of Nanoscale-SiO₂

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摘要 用溶胶-凝胶法制备了纳米SiO₂,考察了溶胶的浓度和pH值对凝胶时间的影响,并用FT-IR,XRD和TEM研究了其在热处理过程中的物相及显微结构.结果表明:溶胶浓度和溶胶pH值对凝胶时间影响较大.在温度为600℃时,经过烧结晶化,可制得纳米二氧化硅,其平均粒径20nm,外观形状呈球形,且热稳定性良好.

关键词: [溶胶-凝胶法](#) [纳米SiO₂](#) [正硅酸乙酯\(Si\(OC₂H₅\)₄\)](#)

Abstract: Nanoscale silica were prepared by the Sol-Gel method with CH₃CH₂OH and Si(OC₂H₅)₄. Under different heat-treatment temperatures, the phase and microstructure of the nanoscale silica were studied with FT-IR, XRD and TEM. It is resulted that sol-concentration and its pH value are the important factor which determine the gelation time. Nanoscale-SiO₂ the average diameter is about 20nm and which have acceptable thermal stability were obtained with 600℃ sintering.

Key words: [Sol-Gel method](#) [nanoscale silica](#) [Si\(OC₂H₅\)₄](#)

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